

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Huilong Zhu, et al.

**Examiner:** Chuong A. Luu

**Serial No:** 10/709,239

**Art Unit:** 2892

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**Docket:** FIS920030375US1 (17192)

**For:** STRUCTURES AND METHODS FOR  
MANUFACTURING OF DISLOCATION  
FREE STRESSED CHANNELS IN BULK  
SILICON AND SOI CMOS DEVICES BY  
GATE STRESS ENGINEERING WITH  
SiGe AND/OR Si:C

**Dated:** June 20, 2008

**Confirmation No:** 3238

Commissioner for Patents  
United States Patent Office  
Alexandria, VA 23313-1450

**RESPONSE UNDER 37 C.F.R. § 1.111**

Sir:

In response to the Office Action dated March 20, 2008, Applicants submit the following amendments and remarks for entry of record in the above-identified patent application.

**Amendments to the Claims** are provided in the **Listing of Claims** beginning on page 2 of this paper.

**Remarks** begin on page 9 of this paper.

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**CERTIFICATE OF ELECTRONIC FILING**

I hereby certify that this correspondence is being deposited with the United States Patent & Trademark Office via Electronic Filing through the United States Patent and Trademark Office e-business website, on June 20, 2008.

Dated: June 20, 2008

  
Harry Andrew Hild Jr.